Serial No.: 10/565,429

Filing Date: January 18, 2006

Customer No.: 26,289 Attorney's Docket No.: 2003JP317

Complete set of Claims

[1] (currently amended) A coating composition comprising: a polyalkylsilazane compound; an acetoxysilane compound; and an organic solvent; where said polyalkylsilazane compound contains one or both groups represented by formulae (2) and (3)

$$-\left(\stackrel{R^{8}}{N} - \stackrel{R^{9}}{\stackrel{|}{\sum}} - R^{10}\right)$$
 (3)

wherein R⁵ to R¹¹ each independently represent a hydrogen atom or an alkyl group having 1 to 3 carbon atoms, provided that both R⁵ and R⁶ do not simultaneously represent hydrogen and all of R⁹ to R¹¹ do not simultaneously represent hydrogen, and further where the acetoxysilane compound is selected from tetraacetoxysilane, methyltriacetoxysilane, ethyltriacetoxysilane, ethyltriacetoxysilane, isopropoxytriacetoxysilane, n-butoxytriacetoxysilane, dimethyldiacetoxysilane, diethyldiacetoxysilane, diethyldiacetoxysilane, diethoxydiacetoxysilane, diethoxyacetoxysilane, diethoxyacetoxysilane, diisopropoxydiacetoxysilane, diethoxyacetoxysilane, diisopropoxydiacetoxysilane, and di-n-butoxydiacetoxysilane.

- [2] (original) The coating composition according to claim 1, which further comprises a pore forming agent.
- [3] (currently amended) The coating composition according to claim 2, wherein said pore forming agent is a copolymer comprising a siloxy-containing polyethylene

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oxide compound er-a silexy containing polyethylene exide-compound as monomer units.

- [4] (cancel)
- [5] (withdrawn) A siliceous material produced by coating a coating composition according to claim 1 onto a substrate or by filling a coating composition according to any one of claims 1 to 4 into a frame or a groove, and firing the coating composition.
- [6] (withdrawn) A semiconductor device comprising a siliceous material according to claim 5 as an intermetal dielectric.
- [7] (withdrawn) A process for producing a siliceous material, comprising heating a coating composition according to claim 1 at a temperature of 350°C or below for 1 to 60 min.
- [8] (cancel).
- [9] (cancel).
- [10] (new) The coating composition according to claim 1, further where the acetoxysilane compound is in the range 5% to 40% by weight ofbased on the weight of the polyalkylsilazane compound.